

Photomask Blank

ABSTRACT

5 A photomask blank including a light-shielding film that has high light-shielding
property and high resistance to SPM cleaning is provided by a light-shielding film
including a protection layer that is provided at the side remotest from the transparent
substrate and composed of a material containing silicon and being free of a transition metal,
and a light-shielding layer that is provided at the transparent substrate-side of the
10 protection layer and composed of a material containing a transition metal and silicon.

[Figure 1]